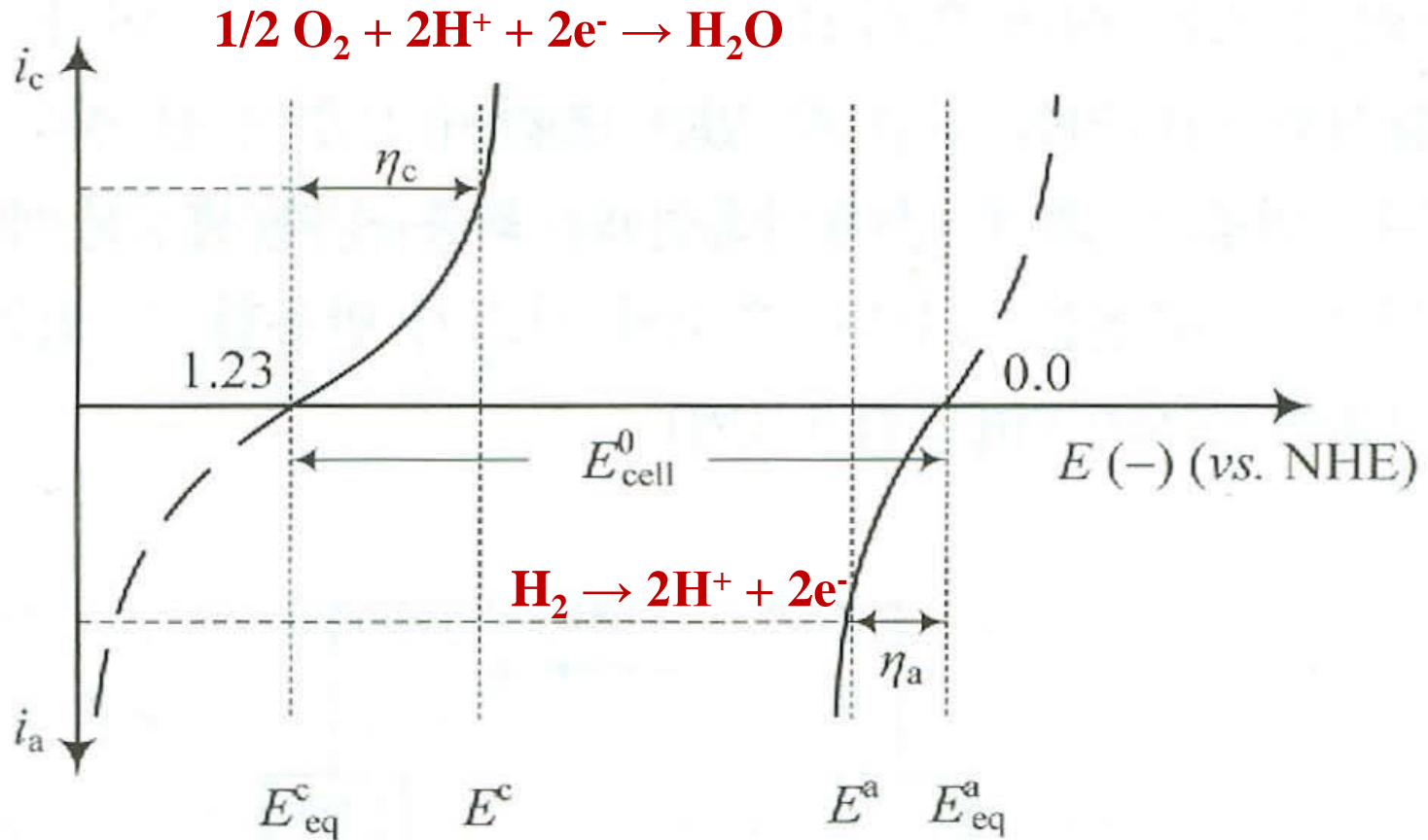


## 16. Photoelectrochemistry (Bard, ch. 18)

A. J. Bard, L. R. Faulkner, *Electrochemical Methods*, Wiley, 2001.

# Electrochemical Energy Devices



**FC/electrolyzer:** hydrogen + oxygen [air]  $\leftrightarrow$  water + electric energy

**Respiration/photosynthesis:** glucose + oxygen (air)  $\leftrightarrow$   $\text{CO}_2$  + water + energy

Photoelectrochemical cell

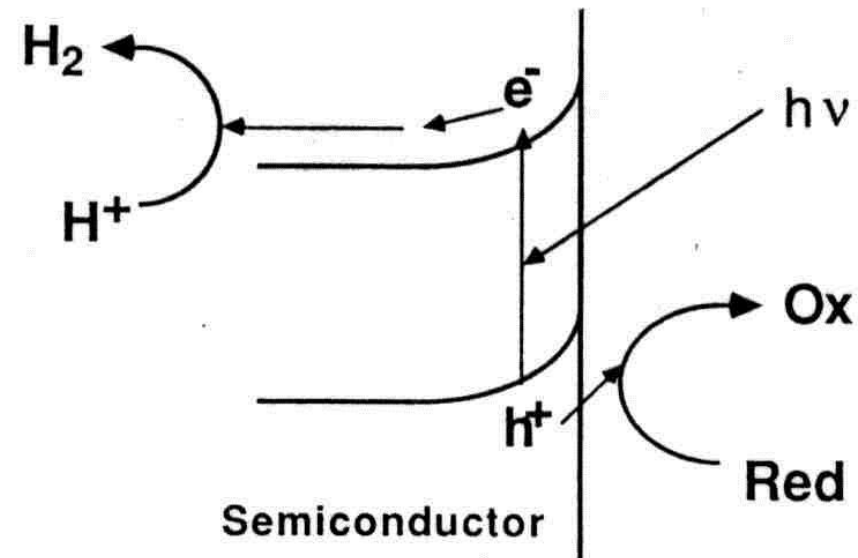
Energy storage (battery)

## Photoelectrochemistry at semiconductors

Radiation energy  $\Leftrightarrow$  electrical or chemical energy

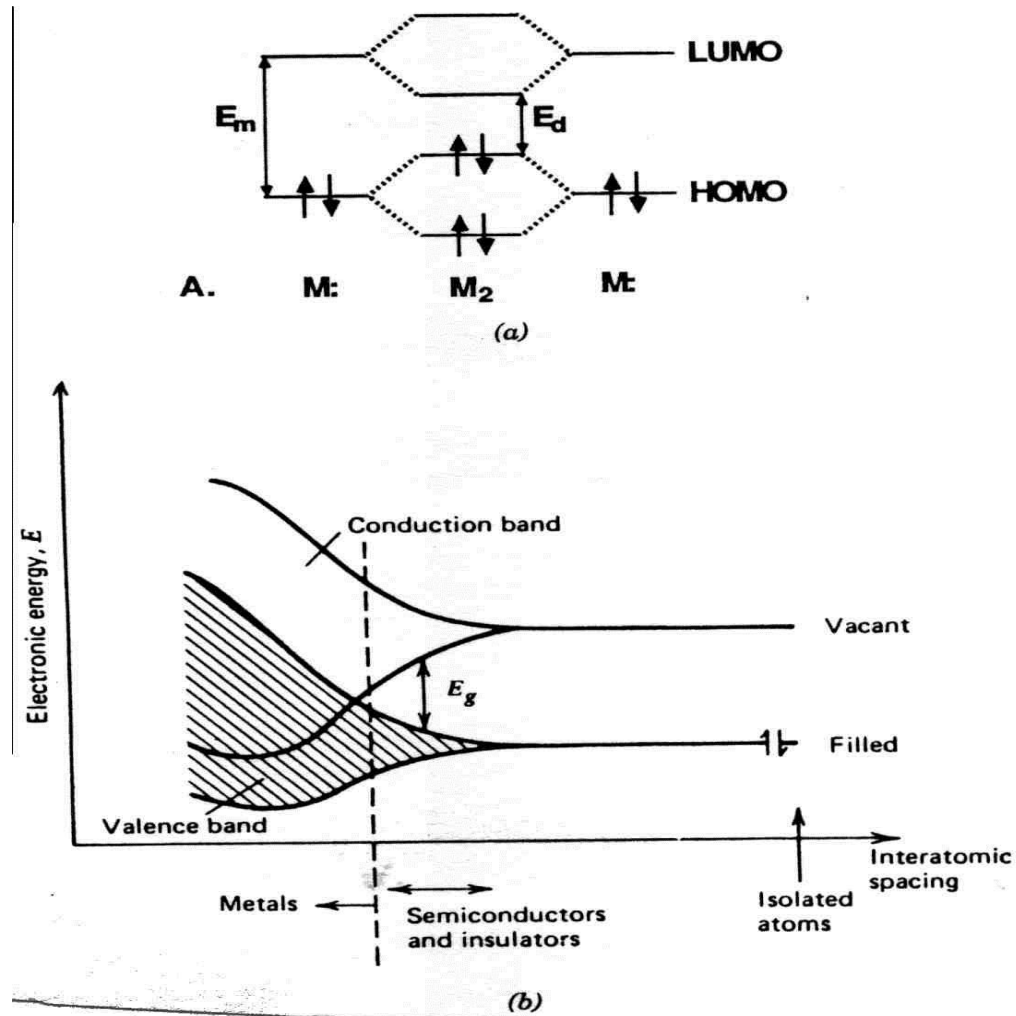
- **photoelectrochemical system:** absorption of light by the system (e.g., sun light)  
→ chemical reactions & flow of current

- semiconductor:  
absorb photons  $\rightarrow$  electron-hole pairs  $\Rightarrow$  oxidation/reduction reactions  $\rightarrow$  products  
(photocurrent)

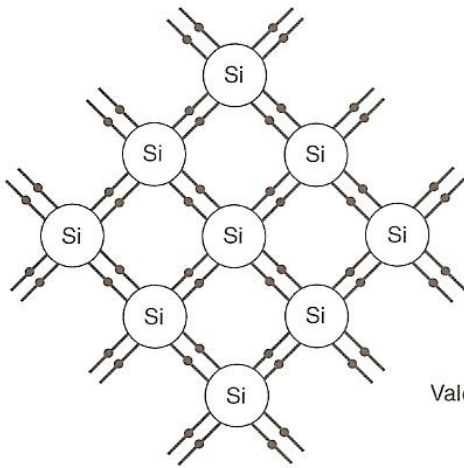
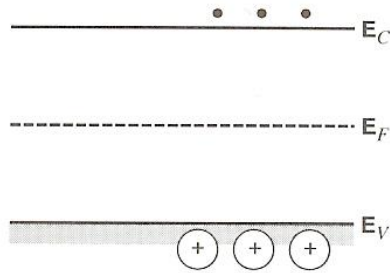
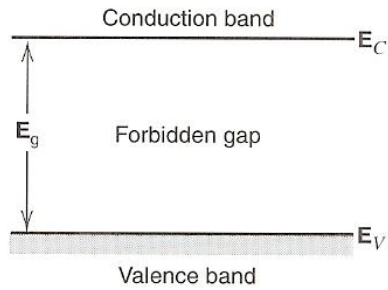


# Semiconductor electrodes

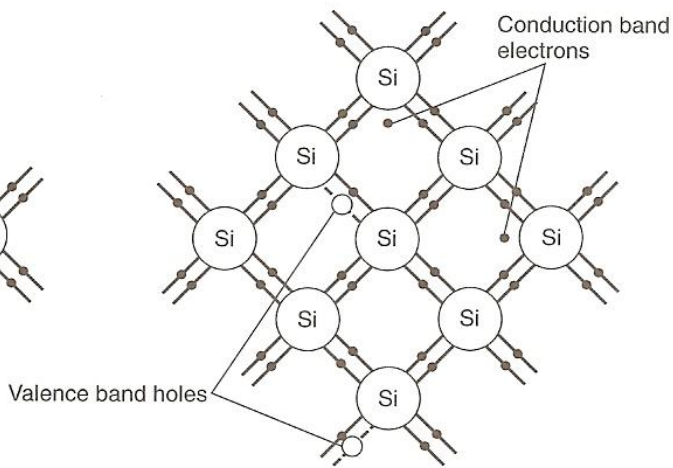
## Band model



# intrinsic semiconductor; undoped



(a)



(b)

- intrinsic semiconductor; # of  $e^- (n_i)$  &  $h^+ (p_i)$  per  $\text{cm}^3$  at T

---

$$n_i = p_i = (N_C N_V)^{1/2} \exp \left[ -\frac{E_g}{2kT} \right]$$
$$N_C = 2 \left( \frac{2\pi m_n kT}{h^2} \right)^{3/2} = (4.83 \times 10^{15}) (m_e^* T)^{3/2}$$
$$N_V = 2 \left( \frac{2\pi m_p kT}{h^2} \right)^{3/2} = (4.83 \times 10^{15}) (m_h^* T)^{3/2}$$

Where T(K),  $m_n$ ,  $m_p$ ; reduced masses of  $e^-$  &  $h^+$ ,  $m_e^*$ ,  $m_h^*$ ; relative effective masses where  $m_e^* = m_n/m_0$ ,  $m_h^* = m_p/m_0$  ( $m_0$ ; rest mass of an electron)

$$n_i = p_i \sim 2.5 \times 10^{19} \exp(-E_g/2kT) \text{ cm}^{-3} \text{ (near } 25^\circ\text{C)}$$

For Si,  $n_i = p_i \sim 1.4 \times 10^{10} \text{ cm}^{-3}$

$E_g > 1.5 \text{ eV} \rightarrow$  few carriers: electrical insulators

TABLE 6.2.1. Energy Gaps ( $E_g$ ) of Selected Materials

Substance	$E_g$ (eV)	Substance	$E_g$ (eV)
Ge	0.67	Fe <sub>2</sub> O <sub>3</sub>	~ 2.3
CuInSe <sub>2</sub>	0.9	CdS	2.42
Si	1.12	ZnSe	2.58
WSe <sub>2</sub>	~ 1.1	WO <sub>3</sub>	2.8
MoSe <sub>2</sub>	~ 1.1	TiO <sub>2</sub> (rutile)	3.0
InP	1.3	TiO <sub>2</sub> (anatase)	3.2
GaAs	1.4	ZnO (zincite)	3.2
CdTe	1.50	SrTiO <sub>3</sub>	3.2
CdSe	1.74	SnO <sub>2</sub>	3.5
GaP	2.2	ZnS (zinc blende)	3.54
		C (diamond)	5.4

TABLE 6.2.2. Properties of Si and GaAs

Property	Si	GaAs
Atoms/cm <sup>3</sup>	$5.0 \times 10^{22}$	$2.21 \times 10^{22}$
$E_g$ (eV) at 300 K	1.12	1.43
Crystal structure	Diamond	Zinc blende
Density (g/cm <sup>3</sup> )	2.328	5.32
Effective density of states in conduction band, $N_C$ (cm <sup>-3</sup> )	$2.8 \times 10^{19}$	$4.7 \times 10^{17}$
Effective density of states in valence band, $N_V$ (cm <sup>-3</sup> )	$1.02 \times 10^{19}$	$7.0 \times 10^{18}$
Effective mass ( $m^*/m_0$ )		
Electrons	0.97, 0.19	0.068
Holes	0.16, 0.5	0.12, 0.5
Dielectric constant	11.8	10.9
$n_i, p_i$ (cm <sup>-3</sup> ) at 300 K	$6.8 \times 10^9$	$1.8 \times 10^6$
Mobility (cm <sup>2</sup> V <sup>-1</sup> s <sup>-1</sup> ) at 300 K		
Electrons	1900	8800
Holes	500	400

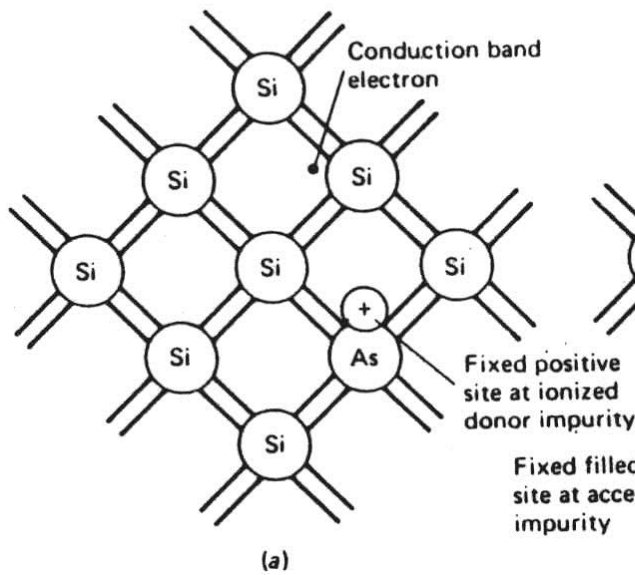
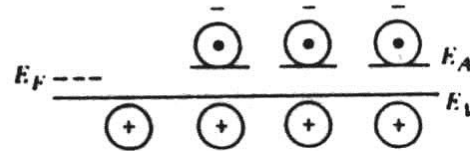
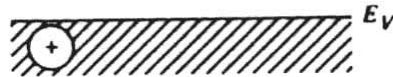
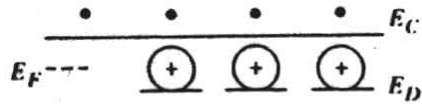
- Mobilities ( $\mu$ , cm<sup>2</sup>V<sup>-1</sup>s<sup>-1</sup>) vs. diffusion coefficient (cm<sup>2</sup>s<sup>-1</sup>)

$$D_i = kT\mu_i = 0.0257\mu \text{ at } 25^\circ\text{C}, \quad i = n, p$$

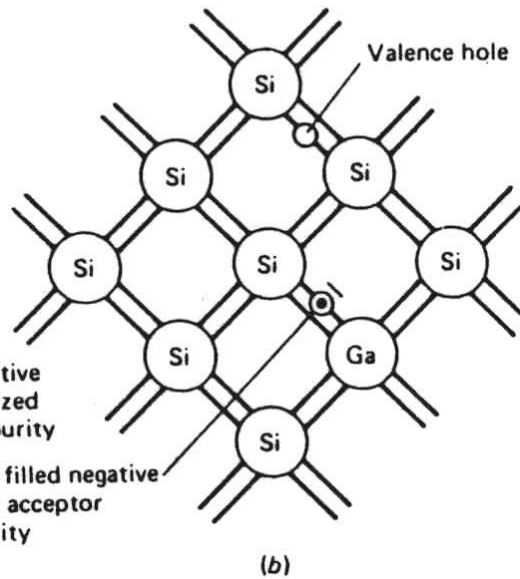


# Extrinsic semiconductors; doped

- dopants or impurity; ~ppm, typical donor densities ( $N_D$ ) are  $10^{15}$ - $10^{17}$   $\text{cm}^{-3}$



n-type



p-type

n-type: total density (n) of electrons in CB

$n = p + N_D$ , p; hole density (thermal activation of VB atoms)

most cases for moderate doping  $N_D \gg p$ ,  $n \sim N_D$

For any materials (intrinsic or extrinsic)

$$np = N_C N_V \exp \frac{-E_g}{kT} = n_i^2 = p_i^2$$

For n-type SC

$$p = \frac{N_C N_V}{N_D} \exp \frac{-E_g}{kT} = \frac{n_i^2}{N_D}$$

e.g.,  $10^{17} \text{ cm}^{-3}$  As doped Si  $\rightarrow$  electron density  $\sim 10^{17} \text{ cm}^{-3}$ , hole density  $\sim 460$   
 $\rightarrow$  majority carrier: electron

p-type

dopant (acceptor) density;  $N_A$ , electron density (by thermal promotion);  $n$   
→

total density of holes ( $p$ )

$$p = n + N_A$$

when  $N_A \gg n$ ,  $p = N_A \rightarrow$  hole; majority carriers

$$n = n_i^2 / N_A$$

e.g., Si:  $N_A = 5 \times 10^{16}$  acceptor/cm<sup>3</sup>,  $n \sim 4000$  cm<sup>-3</sup>

• compound semiconductor (e.g., GaAs or TiO<sub>2</sub>); n-type or p-type → replacement of impurity atoms to the constituent lattice atoms, impurity atoms in an interstitial position, lattice vacancy or broken bond

e.g., n-TiO<sub>2</sub>: oxygen vacancies in the lattice

- extrinsic SC;  $E_F$  move up & down depending upon doping

$$E_F = E_V + kT \ln \left( \frac{N_V}{N_A} \right) \quad (\text{p-type semiconductor})$$

and donors move  $E_F$  up toward the conduction band:

$$E_F = E_C - kT \ln \left( \frac{N_C}{N_D} \right) \quad (\text{n-type semiconductor})$$

e.g.,  $10^{17} \text{ cm}^{-3}$  As doped Si  $\rightarrow N_D \sim 10^{17} \text{ cm}^{-3}$ ,  $N_C = 2.8 \times 10^{19} \text{ cm}^{-3}$ ,  $25 \text{ }^\circ\text{C}$

$$\Rightarrow E_F = E_C - (25.7 \times 10^{-3} \text{ eV}) \ln(N_C/N_D) \sim E_C - 0.13 \text{ eV}$$

- if  $N_D < N_C$ ,  $N_A < N_V \rightarrow \text{SC}$

- if higher doping levels; Fermi level moves into VB or CB  $\Rightarrow$  show metallic conductivity

e.g., transparent  $\text{SnO}_2$  ( $E_g = 3.5 \text{ eV}$ ) + heavily doping with Sb(III) ( $N_D > 10^{19} \text{ cm}^{-3}$ )  $\Rightarrow$  the material becomes conductive

## Fermi level

1) probability that an electronic level at energy  $E$  is occupied by an electron at thermal equilibrium  $f(E) \rightarrow$  Fermi-Dirac distribution function

$$f(E) = \frac{1}{1 + \exp [(E - E_F)/kT]}$$

- Fermi level  $E_F$ ; value of  $E$  for which  $f(E) = 1/2$  (equally probable that a level is occupied or vacant)
- At  $T = 0$ , all levels below  $E_F$  ( $E < E_F$ ) are occupied ( $f(E) \rightarrow 1$ ); all levels  $E > E_F$  vacant
- intrinsic SC:  $E_F$  in the middle of CB and VB edges

2) alternative definition of  $E_F$  for a phase  $\alpha$  : “electrochemical potential”

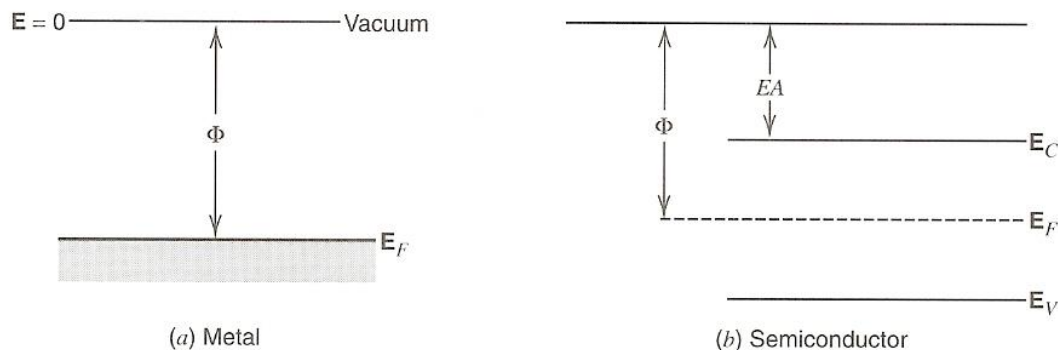
$$E_F^\alpha = \bar{\mu}_e^\alpha = \mu_e^\alpha - ze\phi^\alpha$$

where  $\bar{\mu}_e^\alpha$  is the *electrochemical potential* of electrons in phase  $\alpha$ ,  $\mu_e^\alpha$  is the chemical potential of electrons in this phase, and  $\phi^\alpha$  is the inner potential of  $\alpha$  (related to the electrical potential applied to the phase).

- useful in thermodynamic considerations of reactions and interfaces; at equilibrium electrically, the electrochemical potential of electrons in all phases must be same by charge transfer  $\rightarrow$  same Fermi level
- Fermi levels difference between two phases; function of the applied potential

• Fermi level (uncharged phase) vs. work function ( $\Phi$ )

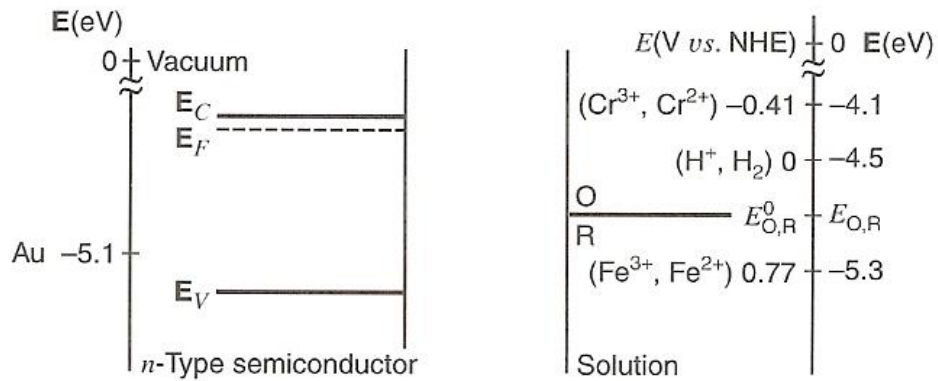
$$\Phi = -E_F$$



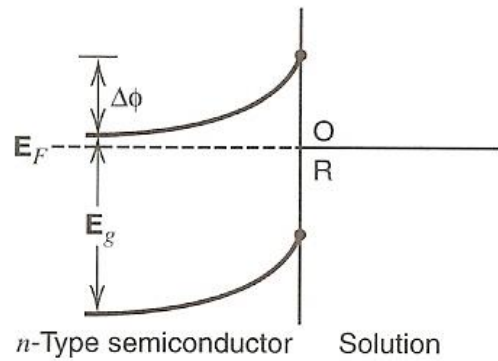
## Semiconductor/solution interface

- electron transfer at the interface (same principles as those given above) + chemical reaction (if possible, e.g., decomposition of SC, oxide film formation) → complicate
  - Si; SiO<sub>2</sub> (if oxygen or oxidant in solution); hinder electron transfer
- The distribution of charge (e<sup>-</sup>/h<sup>+</sup> in SC & ions in solution) and potential; depend on their relative Fermi level
- Fermi level in solution: electrochemical potential of electrons in solution phase ( )
  - governed by the nature and concentration of the redox species present in the solution and is directly related to the solution redox potential as calculated by the Nernst equation
  - at the point of zero charge, no surface state, no specifically adsorbed ions, no excess charge → the distribution of carriers (e<sup>-</sup>, h<sup>+</sup>, anions, cations) is uniform from surface to bulk, and the energy bands are flat “ flat band potential” (E<sub>fb</sub>) ; no space charge layer in SC & no diffuse layer in solution

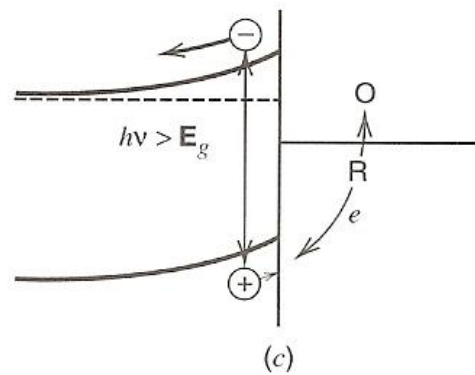
# n-type



(a)



(b)



(c)



- potential difference (by applied voltage or Fermi level difference) ; charged interface → space charge layer (thickness  $W$ ); potential difference  $\Delta V$ , dopant density  $N_D$

$$W \text{ (cm)} \approx 1.05 \times 10^3 \left[ \frac{\epsilon \Delta V \text{ (V)}}{N_D \text{ (cm}^{-3}\text{)}} \right]^{1/2}$$

50 ~ 2000 Å

- band bending: because of non uniform carrier density in SC (upward (with respect to the bulk SC) for a positively charged SC and downward for a negatively charged one) → electric field in the space charge region → direction of motion

## The capacitance of the space charge layer

$$C_{sc} = (2kTn_i \epsilon \epsilon_0)^{1/2} \cdot \frac{e}{2kT} \frac{-\lambda e^{-Y} + \lambda^{-1} e^Y + (\lambda - \lambda^{-1})}{[\lambda(e^{-Y} - 1) + \lambda^{-1}(e^Y - 1) + (\lambda - \lambda^{-1})]^{1/2}}$$

where  $\lambda = n_i/N_D$  and  $Y = e\Delta\phi/kT$ . This equation can be simplified under the conditions that a depletion layer exists (i.e.,  $\lambda e^{-Y} \ll \lambda^{-1}$ ). For an n-type semiconductor, when  $\lambda^{-1} \gg \lambda$ , this equation can be written with some rearrangement as

$$\frac{1}{C_{sc}^2} = \frac{2}{e\epsilon\epsilon_0 N_D} \left( -\Delta\phi - \frac{kT}{e} \right) \quad \text{Mott-Schottky plot}$$

which at 25°C, for  $C_{sc}$  in  $\mu\text{F}/\text{cm}^2$ ,  $N_D$  in  $\text{cm}^{-3}$ , and  $\Delta\phi = E_{fb} - E$  in volts is

$$\frac{1}{C_{sc}^2} = \frac{1.41 \times 10^{20}}{eN_D} [E - E_{fb} - 0.0257]$$

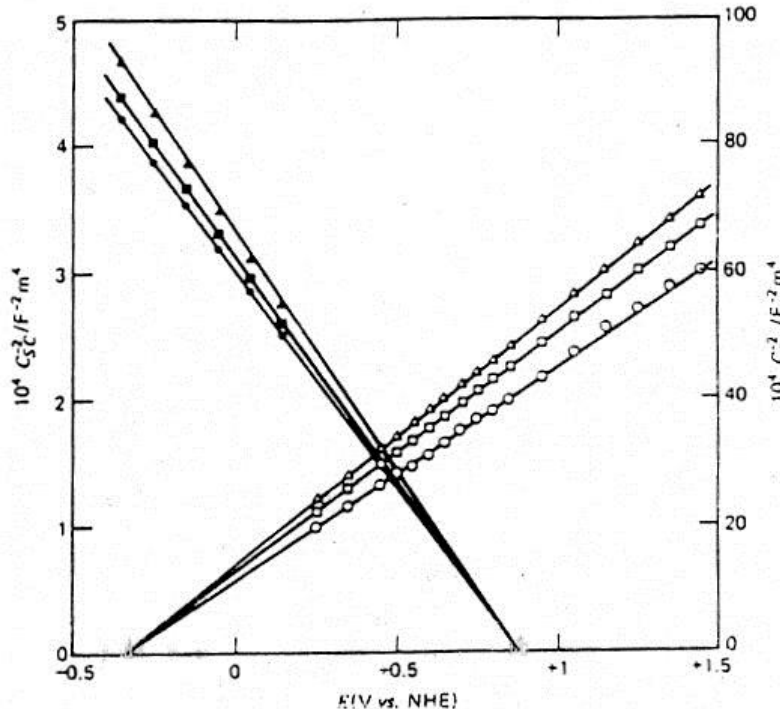
Mott-Schottky plot: useful in characterizing SC/liquid interface where a plot of  $(1/C_{sc}^2)$  vs.  $E$  should be linear  $\rightarrow$  values of  $E_{fb}$  and  $N_D$  from the intercept and slope

space charge capacitance  $C_{sc}$  → Mott-Schottly equation

$$1/C_{sc}^2 = (2/e\epsilon\epsilon_0N)^{1/2}(-\Delta\phi - kT/e)$$

$\epsilon$ : dielectric constant,  $N$ : donor or acceptor densities,  $e$ : quantity of charge, -  
 $\Delta\phi = E - E_{fb}$

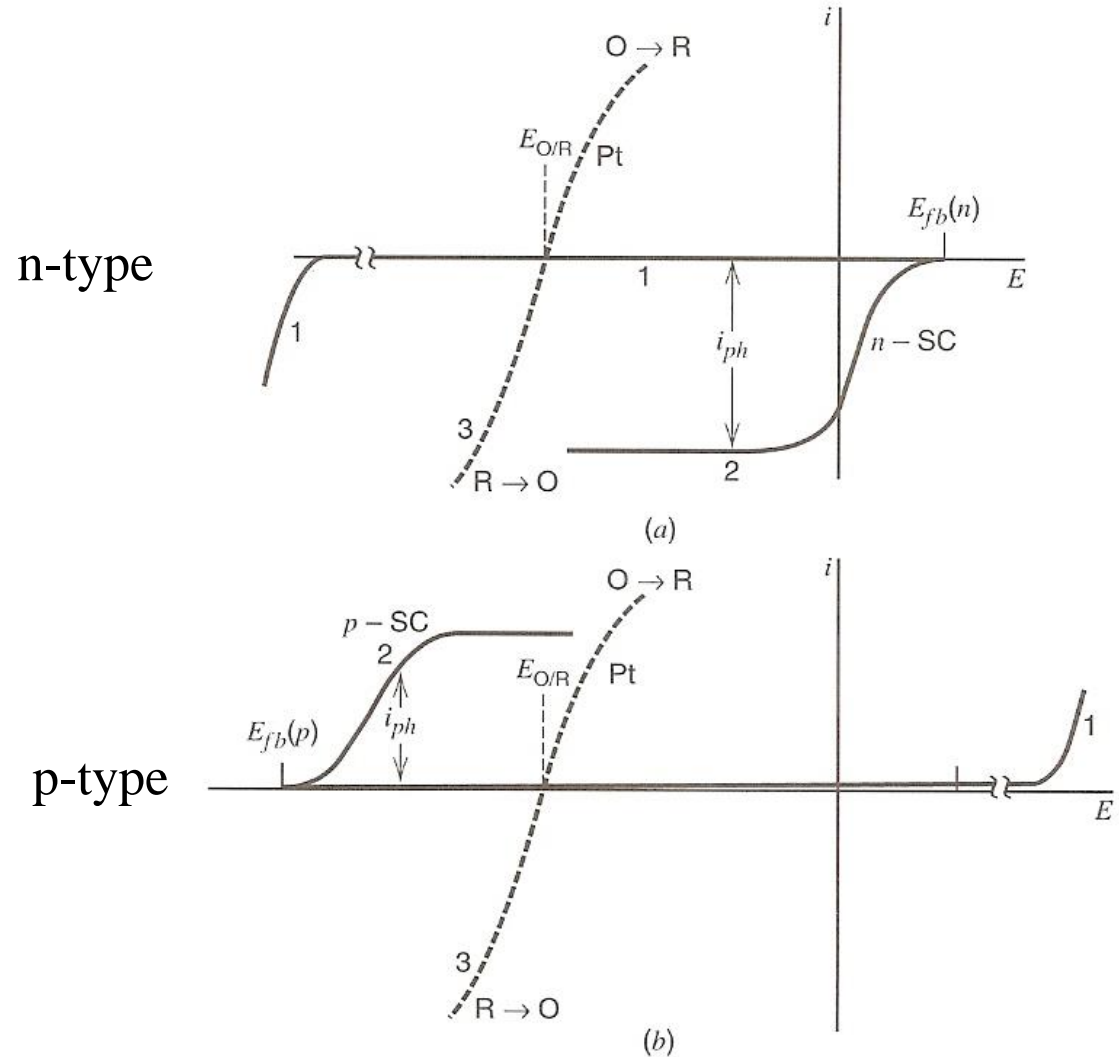
A plot of  $1/C_{sc}^2$  vs. potential  $E$  should be linear →  $E_{fb}$ , doping level  $N$



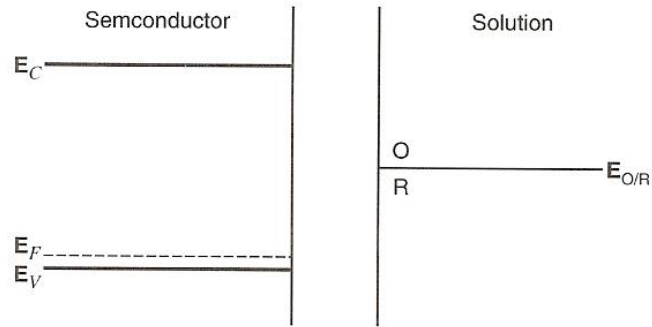
**Mott-Schottky plots for n- and p-type  
InP  
in 1 M KCl + 0.01 M HCl**

# Photoeffects at semiconductor electrodes

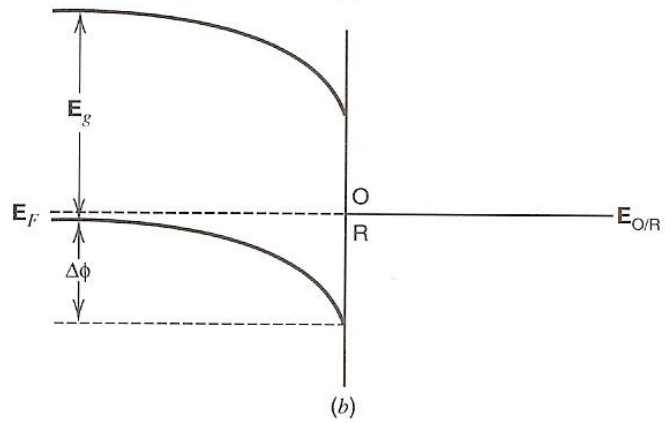
- 1: dark
- 2: irradiation
- 3: Pt electrode



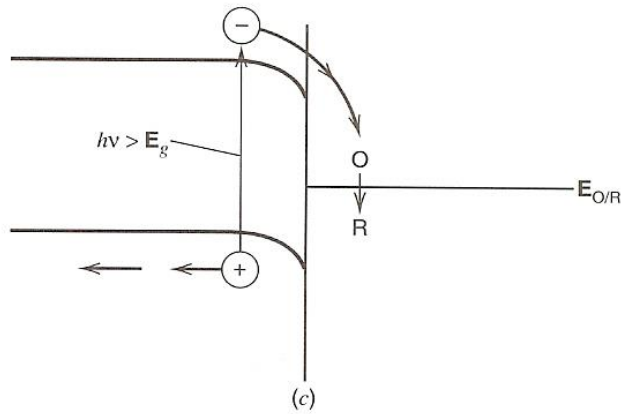
p-type



(a)



(b)



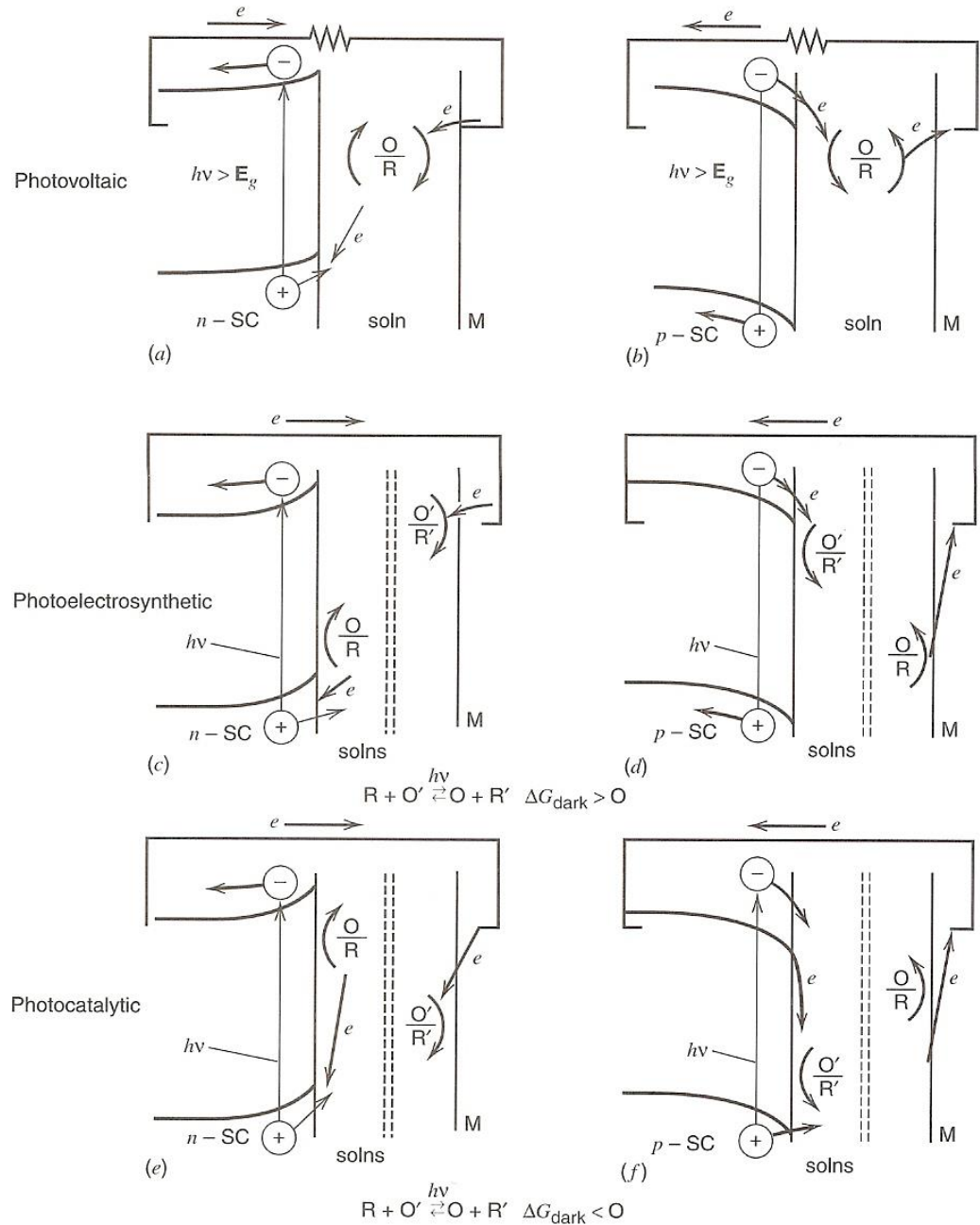
(c)

# Photoelectrochemical cells

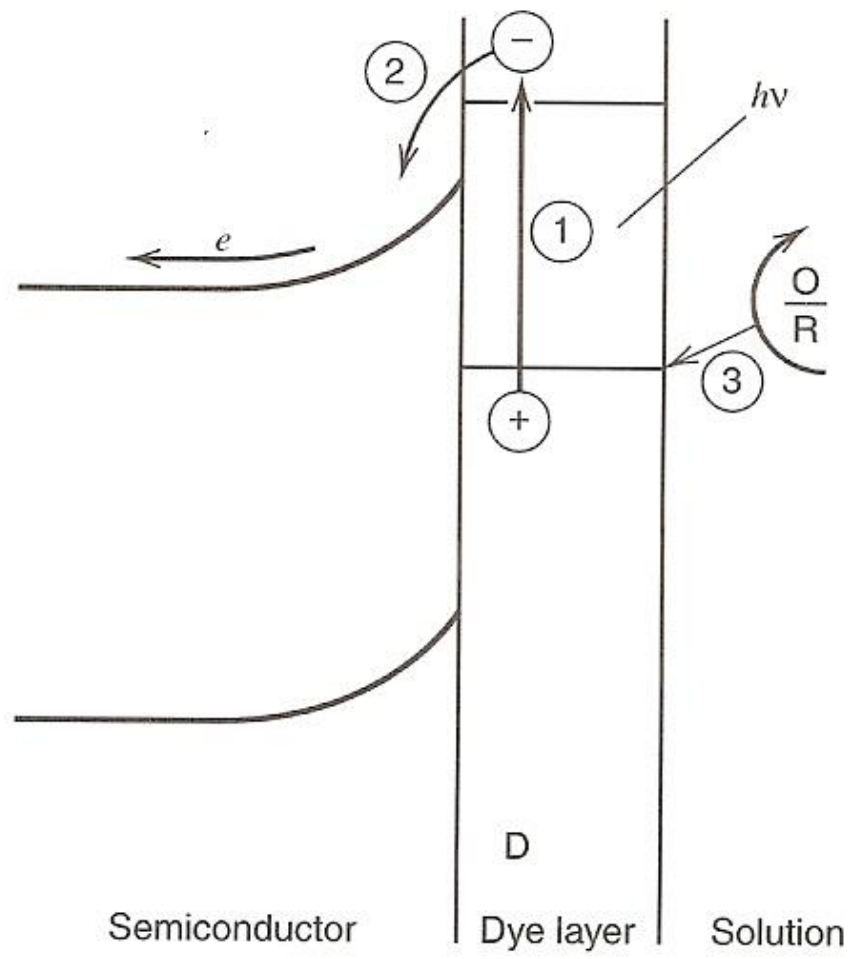
Photovoltaic cells:  
convert light to electricity

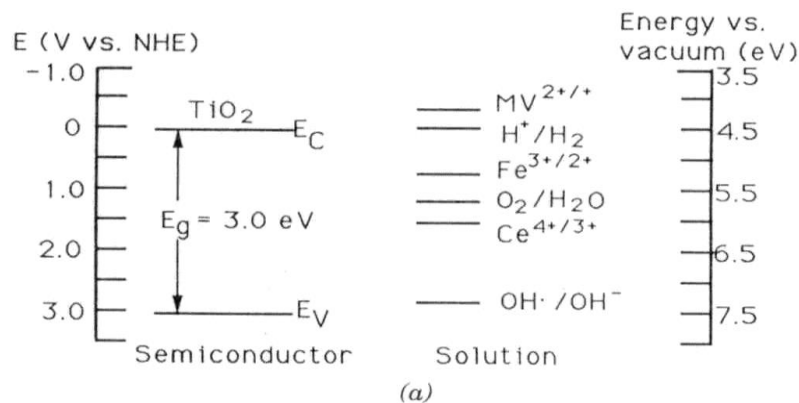
Photoelectrosynthetic cells:  
Radiant E to chemical energy

Photocatalytic cells:  
Light E to overcome  
activation E of the process

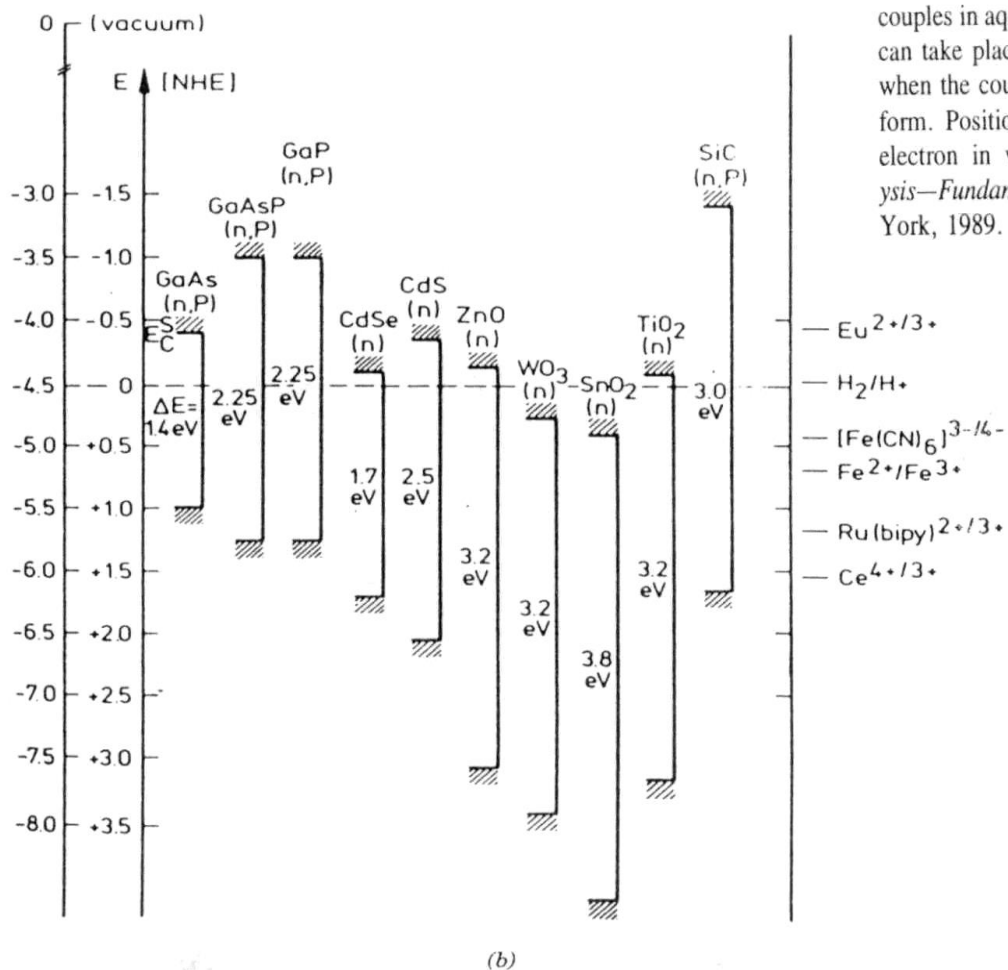


Band gap vs. wavelength  $\rightarrow$  limit to utilize sunlight (e.g.,  $\text{TiO}_2$  (3.0 eV))  
 $\rightarrow$  dye sensitization of a semiconductor



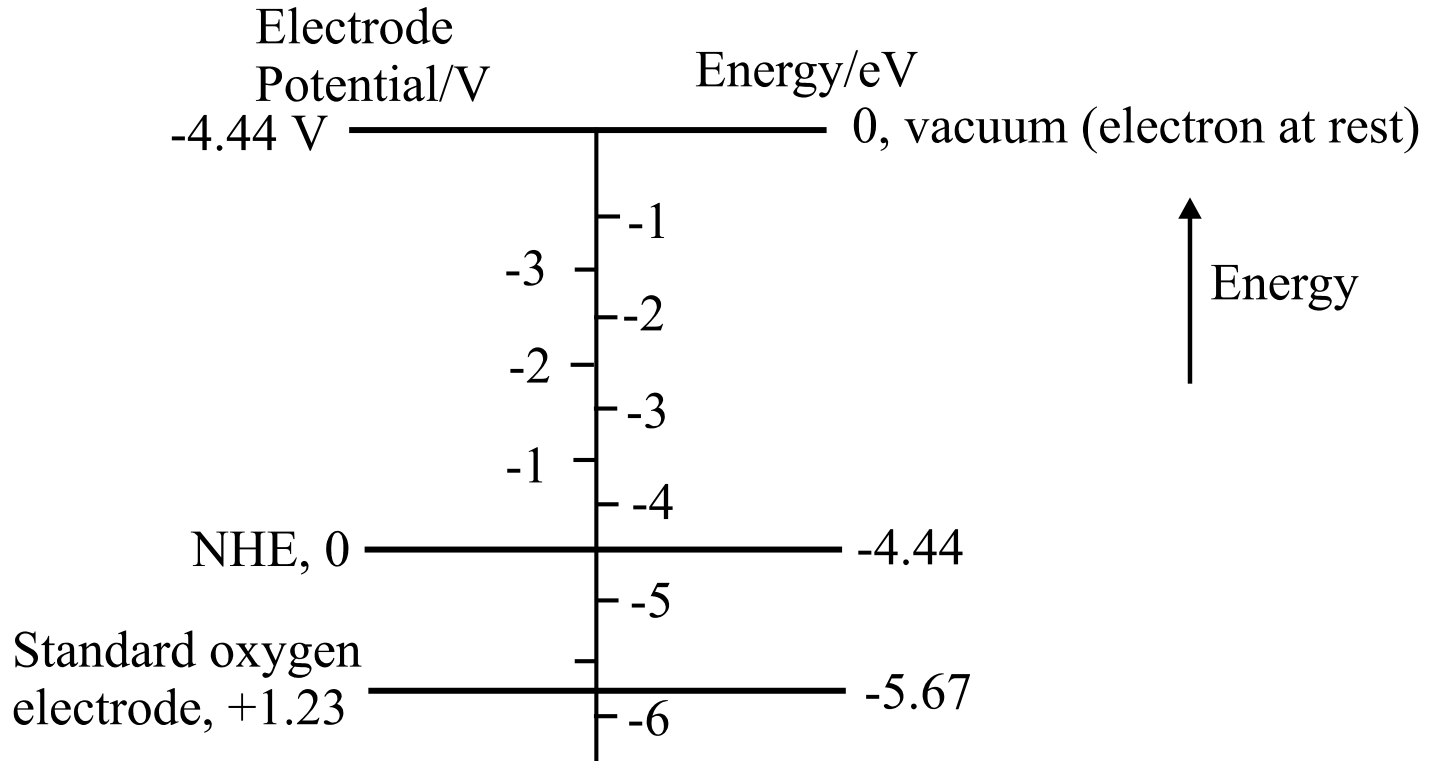


Band-edge positions of semiconductors with respect to several redox couples in aqueous solution at pH 1. (a)  $\text{TiO}_2$  in rutile form. Reduction by a CB electron can take place when the redox couple lies below  $E_C$ ; oxidation by a VB hole occurs when the couple lies above  $E_V$ . (b) Other semiconductors; here  $\text{TiO}_2$  is in the anatase form. Positions are given both as potentials versus NHE and as energies versus the electron in vacuum. [Reprinted with permission from M. Grätzel, in *Photocatalysis—Fundamentals and Applications*, N. Serpone and E. Pelizzetti, eds., Wiley, New York, 1989. Copyright © 1989 John Wiley & Sons.]





## Potential vs. energy (vs. vacuum)



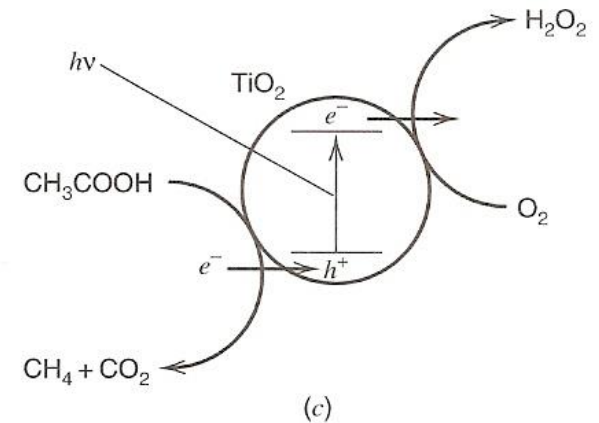
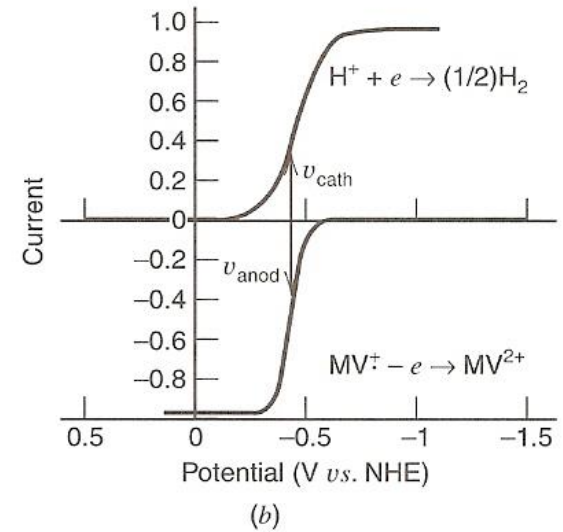
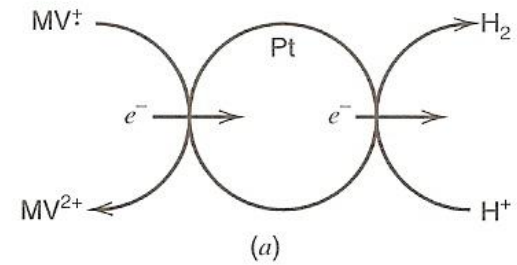
# Semiconductor particles

Grains

Nanocrystalline films

Quantum particles

(Q-particles or quantum dots)



# I-V Curves in Fuel Cell, Battery, Solar Cell(Photoelectrochemical Cell)

